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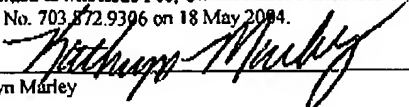
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Application Serial No. 10/085,759

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In re Application of inventor:

Michel L. Cote et al.

Application No. 10/085,759

Confirmation: 1994

Filing Date: 28 February 2002

Title: **Design and Layout of Phase Shifting
Photolithographic Masks**

Group Art Unit: 1756

Examiner: Stephen D. Rosasco

Customer No. 30437

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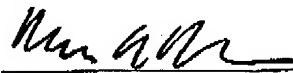
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It is respectfully requested that this new PTO Form SB-08 be placed in the record...

Respectfully submitted,

Date:

18 May 2004



Mark A. Haynes, Reg. No. 30,846

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Substitute for form 1449B/PTO			Complete if Known		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)			Application Number	10/085,759	
			Filing Date	28 February 2002	
			First Named Inventor	Michel L. Cote	
			Group Art Unit	1756	
			Examiner Name	Stephen D. Rosasco	
Sheet	1	of	3	Attorney Docket Number	NMTI 1002-6

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	C1	SAKATA, MIWA, et al., "A Novel Radiation Sensitive Spin-on-glass Convertible into SiO ₂ and the Simple Fabrication Process Using It," 26 July 1993* (*ATI Bell Labs fax date), 3 pages.	
	C2	PISTOR, THOMAS V., "Rigorous 3D Simulation of Phase Defects in Alternating Phase-Shifting Masks," Proceedings of SPIE 4562-1038 (March 2002), 13 pages	
		OGAWA, KIYOSHI, et al., "Phase Defect Inspection by Differential Interference," Proceedings of SPIE 4409-71, 26 April 2001, 12 pages.	
		RHYNS, P., et al., "Characterization of Quartz Etched PSM Masks for KrF Lithography at the 100 nm node," Proceedings of SPIE 4562 (March 2002), 486-495.	
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		WANG, RUOPING, et al., "Polarized Phase Shift Mask: Concept, Design, and Potential Advantages to Photolithography Process and Physical Design," Proceedings of SPIE 4754-105, 25 April 2002, 12 pages.	
		MATSUOKA, et al., "Application of Alternating Phase-Shifting Mask to 0.16um CMOS Logic Gate Patterns," SPIE Proc. 3051, March 10-14, 1997, 10 pages.	
		SEMMIER, ARMIN, et al., "Application of 3D EMF Simulation for Development and Optimization of Alternating Phase Shifting Masks," Proc. of SPIE 4346-37, 1 March 2001, 12 pages.	
		WONG, ALFRED K., "Polarization Effects in Mask Transmission," Proc. of SPIE 1674, 8 March 1992, 8 pages.	
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		SPENCE, C., et al., "Detection of 60 degree Phase defects on Alternating PSMs," Proc. of SPIE 3412-73, April 1998, 2 pages	

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		SUGAWARA, MINORU, et al., "Defect printability study of attenuated phase-shifting masks for specifying inspection sensitivity," Proc. SPIE 2621-49, September 1995, 16 pages	
		SCHMIDT, REGINA, et al., "Impact of Coma on CD Control for Multiphase PSM Designs," Proc. SPIE 3334-02, February 1998, 11 pages.	
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		ROSENBLUTH, ALAN E., et al., "Optimum Mask and Source Patterns to Print a Given Shape," Proc. SPIE 4346-49, 1 March 2001, 17 pages.	

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		Attorney Docket Number	NMTI 1002-6
Sheet	3	of	3

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		SUZUKI, AKIYOSHI, et al., "Multilevel imaging system realizing k1=0.3 lithography," Proc. SPIE 3679-36, March 1999, 13 pages.	
		VANDENBERGHE, G, et al., "(Sub-) 100nm gate patterning using 248nm alternating PSM," Mentor Graphics White Paper, May 2001, 9 pages	
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		COTE, MICHEL, et al., "A Practical Application of Full-Feature Alternating Phase-Shifting Technology for a Phase-Aware Standard-Cell Design Flow," 1 June 2001, 6 pages	
		HANYU, ISAMU, et al., "New phase-shifting mask with highly transparent SiO2 phase shifters," Proc. SPIE 1264-167, June 1990, pages 166-177.	
		MCCALLUM, MARTIN, et al., "Alternating PSM Mask Performance - A Study of Multiple Fabrication Technique Results," Proc. SPIE 4346-723, September 2001, 6 pages.	

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